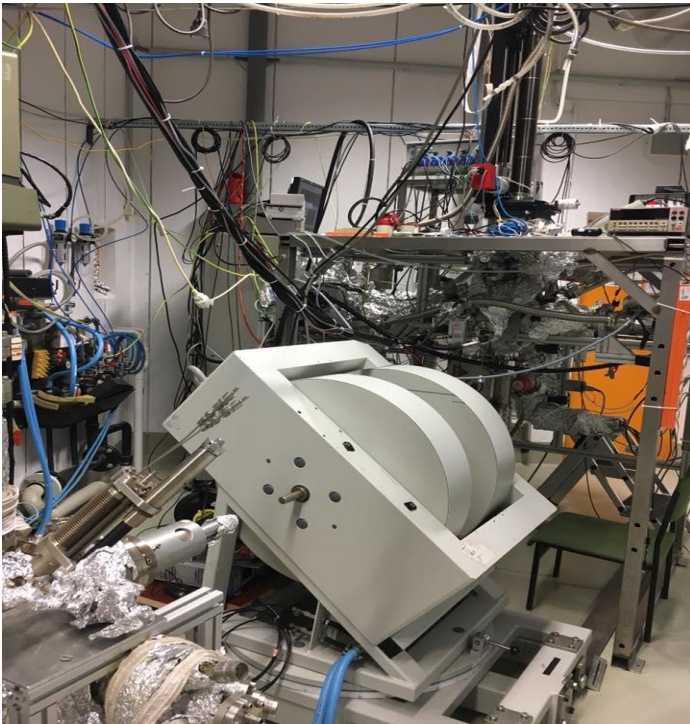


UHV Chamber Experience with DAAD RISE Internship

By Noah Donald



DAAD RISE 
Research Internships
in Science and Engineering

Introduction

- ▶ My Home University: The Ohio State University
- ▶ My Home City: Pittsburgh, Pennsylvania U.S.A
- ▶ Majors: Physics and Mathematics
- ▶ Places I have visited this summer: Amsterdam, Utrecht, Dusseldorf, Munster, Aachen, Koblenz, Bonn, Cologne, Bremen, Heidelberg, Antwerp, Ghent, Brussels, Luxembourg City, Barcelona.

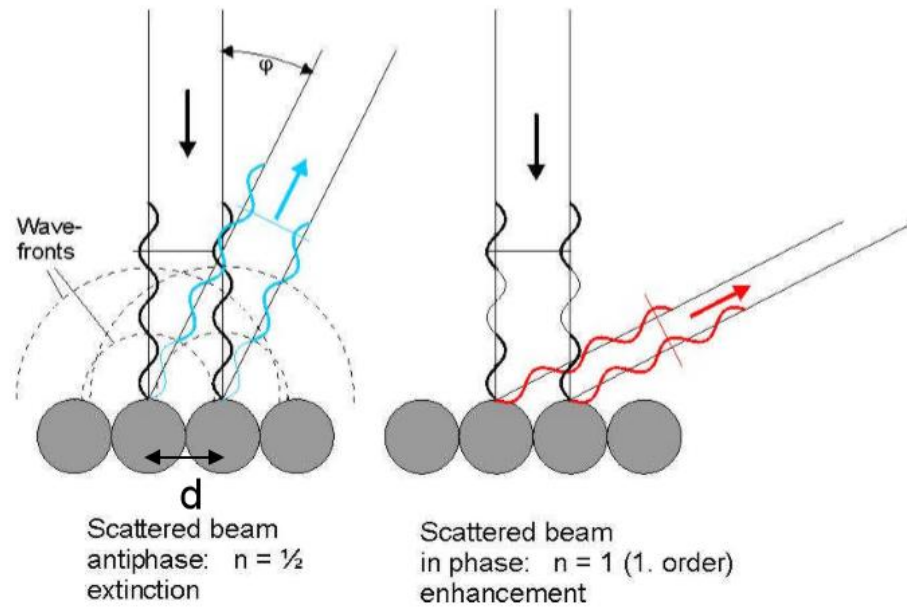


Experiences with UHV Chamber

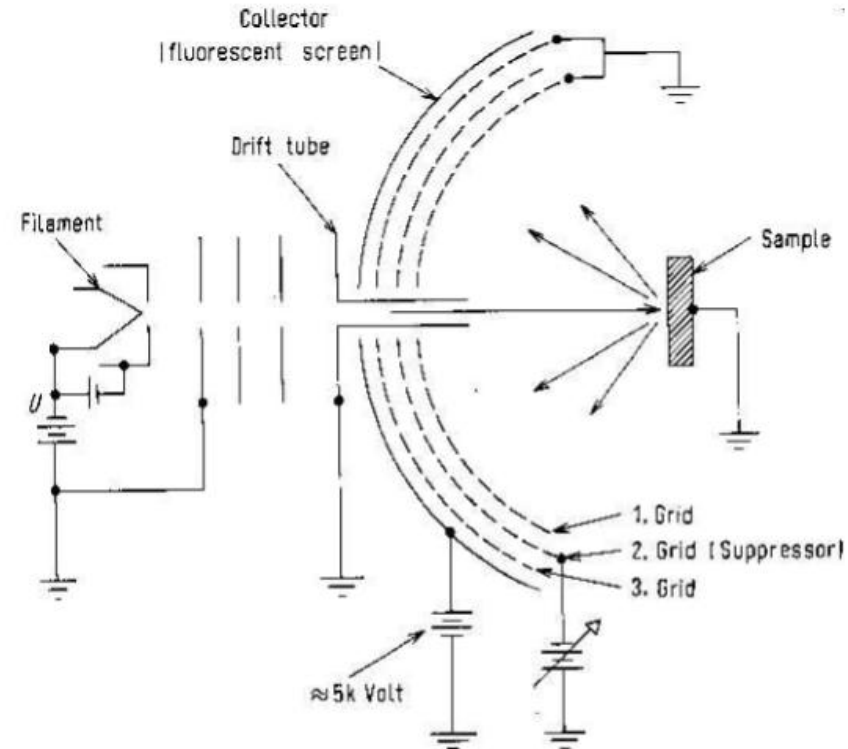
- ▶ Procedures learned:
 - ▶ Preparing Samples
 - ▶ Transferring samples into and out of the chamber
 - ▶ Conducting LEED experiment
 - ▶ Conducting Auger Spectroscopy
 - ▶ Heating and Sputtering
 - ▶ Deposition of thin films on substrates
 - ▶ Bake out
- ▶ How I learned to operate the UHV Chamber:
 - ▶ Writing my own instruction manual: [Lab Instructions.docx](#)



The UHV Chamber: LEED Theory and Setup

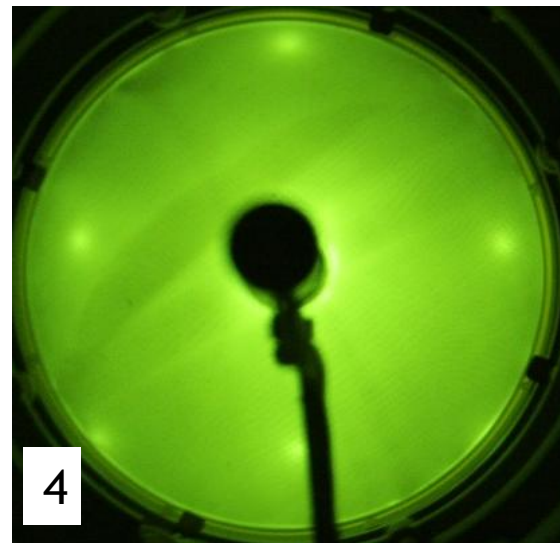
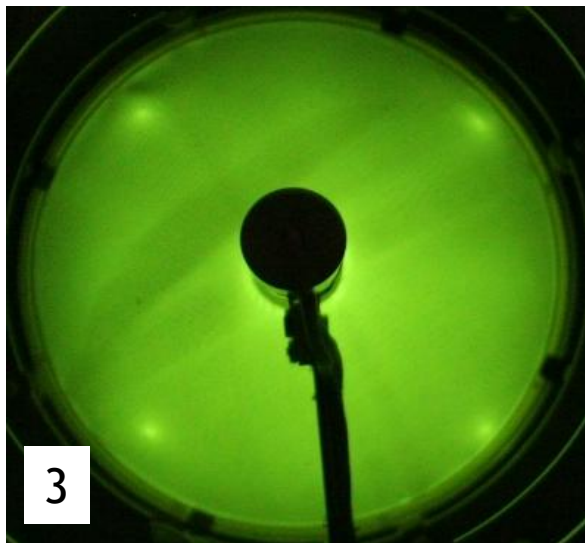
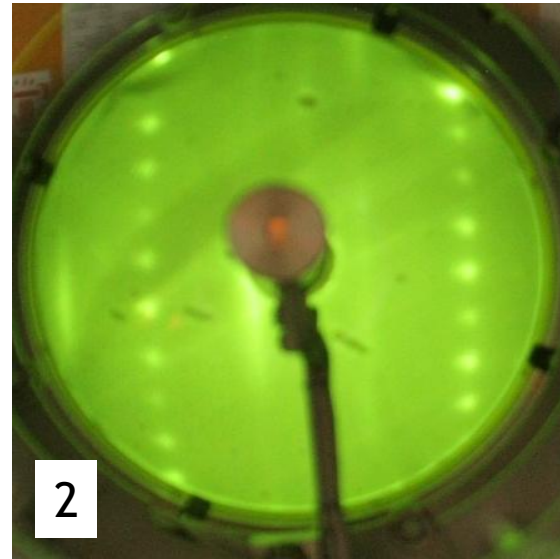
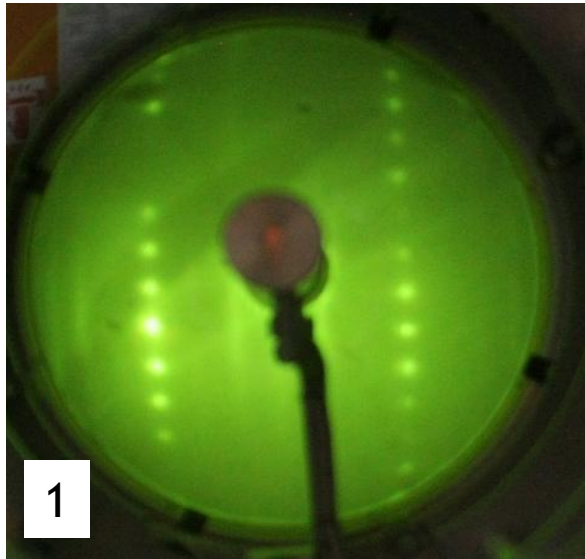


Ertl/Küppers Fig. 9.12, p. 217



Ertl/Küppers fig. 9.7, p. 210

LEED Images and Qualitative Analysis



GaAs[100] after Sputtering and Heating:

1. Image taken at 63 eV on 6/25/2018
 2. Image taken at 28 eV on 6/25/2018
- Pressure: 5.5×10^{-10} mbar

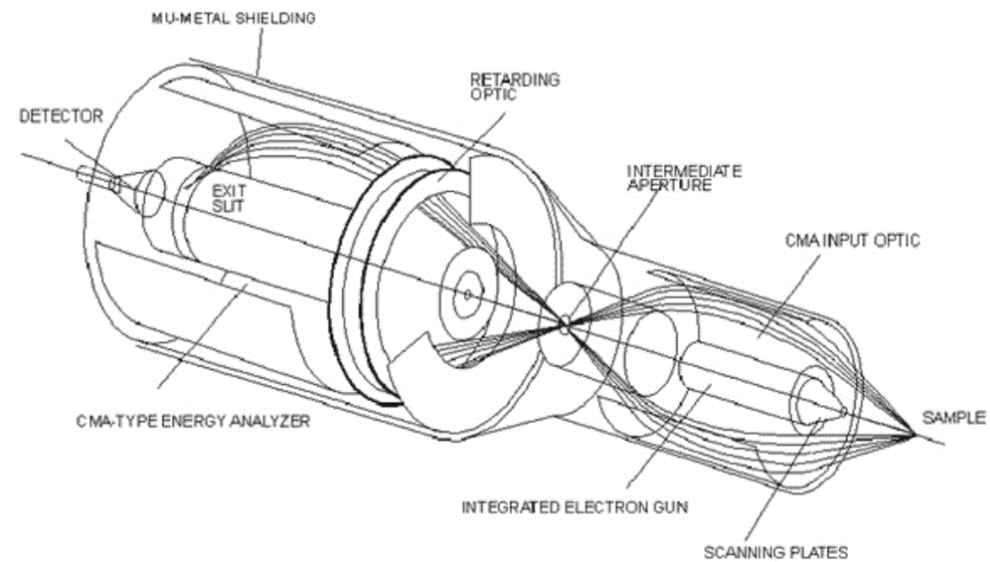
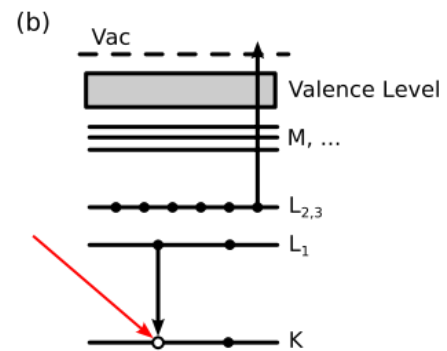
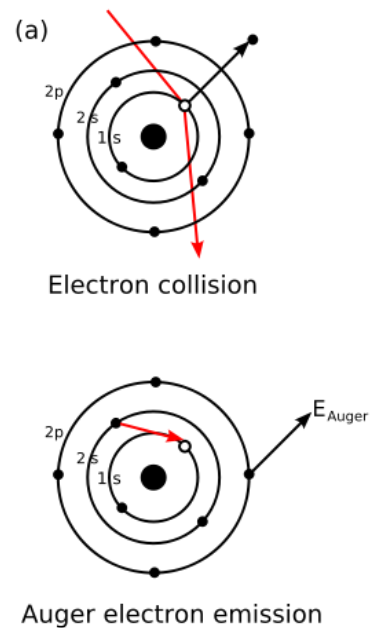
GaAs[100] & 4 nm Fe deposition:

3. Image taken at 117 eV on 6/26/2018
 4. Image taken at 286 eV on 7/2/2018
- Pressure on 6/26/2018: 5.1×10^{-10} mbar
Pressure on 7/02/2018: 2.1×10^{-10} mbar

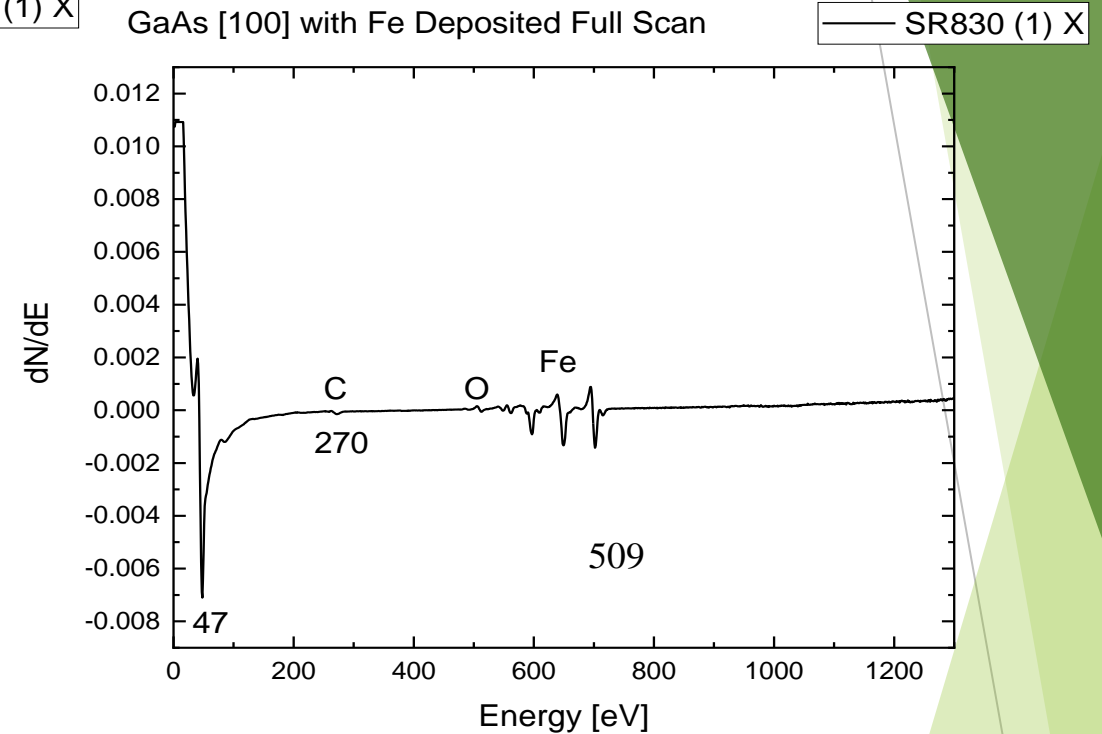
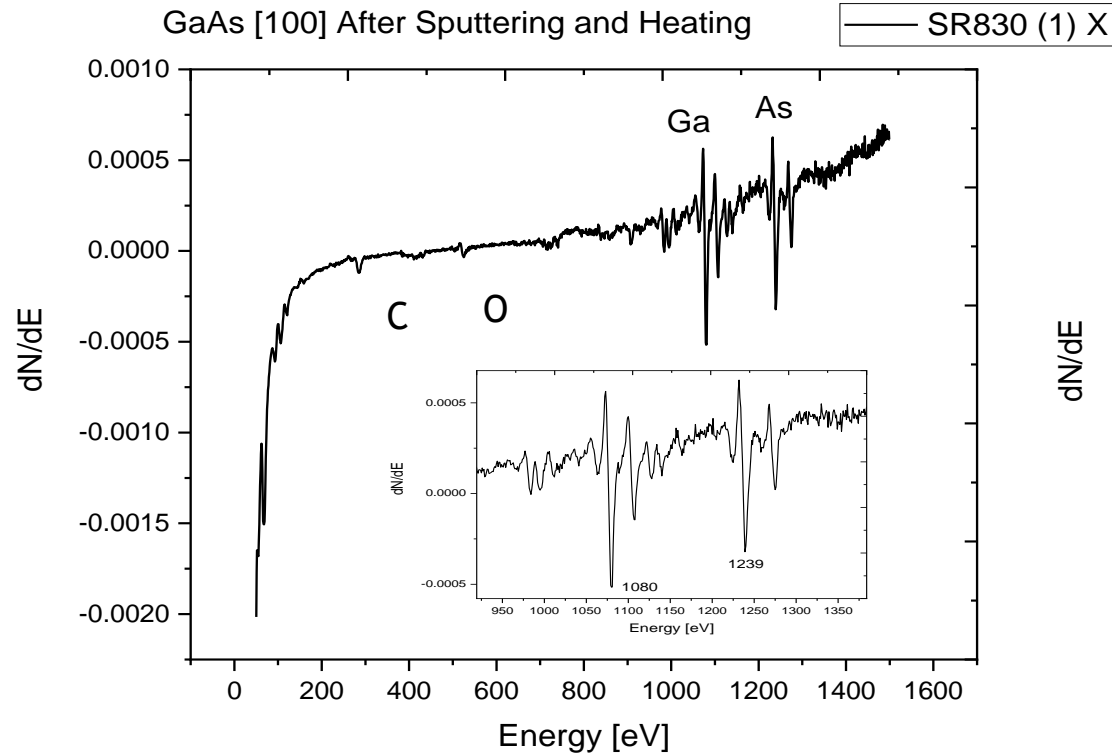
Surface Reconstruction Parameters:

1. Images 1 and 2 show a (1x6) reconstruction
2. Images 3 and 4 show a (2x2) reconstruction

The UHV Chamber: AES Theory and Setup



Analysis of Auger Spectrum



Percent Atomic Mass Concentrations:

Before Deposition:

- Ga: 33.9% ± 3%
- As: 66.1% ± 3%
- O: 1.3% ± 1%
- C: 2.1% ± 1%

After Fe Deposition:

- Fe: 90.9% ± 0.6%
- O: 3.5% ± 0.4%
- C: 5.4% ± 0.5%

Equations:

- $S_x(E_p) = \left(\frac{A+B}{A} \right) \frac{I_x^H}{d_x I_{Ag}^H}$
- $C_x = \frac{I_x}{S_x} \left[\sum \alpha \frac{I_\alpha}{S_\alpha} \right]^{-1}$

Conclusions

- I learned many different procedures and analyses to investigate the atomic level structure and composition of crystalline substrates in the UHV chamber context
- I gained lots of valuable laboratory experience
- The LEED images demonstrate the effect of iron deposition on the substrate, and this is confirmed by the Auger spectroscopy analysis
- I learned a lot about research in Germany, the great people who are doing it, and the vibrant culture this area of Europe has to offer



Thank You!